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	Application No.	Applicant(s)	
	10/046,805	LEE ET AL.	
Notice of Allowability	Examiner	Art Unit	
	Lisa A Kilday	2829	
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The MAILING DATE of this communication appeall claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RID of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in or other appropriate communication is s	n this application. If not included unication will be mailed in due course. <b>T</b> i	<b>HIS</b> iitiative
1. This communication is responsive to <u>TD filed on 2/26/4.</u>			
2. X The allowed claim(s) is/are <u>1-13,34-41 and 60-62</u> .			
3. $\boxtimes$ The drawings filed on <u>27 February 2002</u> are accepted by the	ne Examiner.		
4. Acknowledgment is made of a claim for foreign priority unall All b) Some* c) None of the:  1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)).  * Certified copies not received:  Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.  5. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give 3. CORRECTED DRAWINGS (as "replacement sheets") must (a) including changes required by the Notice of Draftspers 1) hereto or 2) to Paper No./Mail Date  (b) including changes required by the attached Examiner's Paper No./Mail Date  Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in the depose attached Examiner's comment regarding REQUIREMENT in the depose attached Examiner's comment regarding Require	e been received.  been received in Application cuments have been received  of this communication to file ENT of this application.  itted. Note the attached EXA es reason(s) why the oath of the submitted.  con's Patent Drawing Review as Amendment / Comment or the header according to 37 CF sit of BIOLOGICAL MATE	n No  If in this national stage application from the areply complying with the requirements  AMINER'S AMENDMENT or NOTICE Of declaration is deficient.  If (PTO-948) attached  In the Office action of the drawings in the front (not the back) of R 1.121(d).  ERIAL must be submitted. Note the	s
Attachment(s)  1. ☐ Notice of References Cited (PTO-892)  2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)  3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 2/26/4  4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. ☐ Interview So Paper No./ 8), 7. ☐ Examiner's	formal Patent Application (PTO-152)  Jammary (PTO-413),  Mail Date  Amendment/Comment  Statement of Reasons for Allowance	
	En	not thank	
		ERNEST KARLSEN	

## Terminal Disclaimer

The terminal disclaimer filed on 2/26/4 disclaiming the terminal portion of any patent granted on this application, which would extend beyond the expiration date of 6,432,820 has been reviewed and is accepted. The terminal disclaimer has been recorded.

## Allowable Subject Matter

Claims 1-13, 34-41, 60-62 allowed.

The following is an examiner's statement of reasons for allowance: in re claims 1-13, prior art fails to teach or suggest a method of forming a metal layer in an integrated circuit device with the limitation of forming a selective electroplating mask on the sidewall to provide a covered portion of the sidewall and to provide an exposed portion of the sidewall that is free of the selective electroplating mask in combination with the step of electroplating a metal on the exposed portion of the sidewall thus forming an insulation collar or conductive contact in the recess of the integrated device.

In re claims 34-41, prior art does not teach or suggest a method for fabricating a metal layer in a semiconductor device with the limitation of forming a selective electroplating mask inside a portion of a hole/concave portion that covers a portion of the conductive underlying layer and exposes a portion of the conductive underlying layer in combination with selectively electroplating the inside of the hole/concave portion that is exposed.

In re claims 60-62, prior art does not teach or suggest a method of forming a metal layer in an integrated circuit device by forming a recess in a surface of an

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insulating layer, forming a selective deposition mask on the sidewall of the recess where there is a covered portion of the sidewall and an exposed portion of the sidewall in combination with depositing a metal on the exposed portion of the sidewall.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

## Conclusion

Any inquiry of a general nature or relating to the status of this application should be directed to the Group Receptionist whose telephone number is (703) 308-0957. See MPEP 203.08.

Any inquiry concerning this communication from the examiner should be directed to Lisa Kilday whose telephone number is (571) 272-1962. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Kamand Cuneo, can be reached on (571) 272-1957. The fax number for the group is (703) 872-9306. MPEP 502.01 contains instructions regarding procedures used in submitting responses by facsimile transmission.

Lisa Kilday

LAK

4/12/04

ERNEST KARLSEN PRIMARY EXAMINER